

Please substitute the following amended claims for corresponding claims previously presented. A copy of the amended claims showing current revisions is attached.

11. (Unamended) A method of making a reflective liquid crystal display, the method comprising:

providing a substrate;

applying a photosensitive resin on the substrate;

using a single photomask to form both a) asperities in a first region of the photosensitive resin which do not extend all the way through the photosensitive resin, and b) contact holes in a second region of the photosensitive resin, said contact holes extending all the way through the photosensitive resin;

providing said photomask with light transmitting portions, light intercepting portions, and semi-light transmitting portions, so that different amounts of light exposure are utilized using said photomask in order to form at least one of said asperities and said contact holes;

developing the exposed photosensitive resin;

heat treating the developed photosensitive resin; and

forming a reflective electrode on the heat treated photosensitive resin so that said reflective electrode is in electrical communication with a switching element through at least one of said contact holes.

14. (Amended) A method of making a reflective liquid crystal display, the method comprising:

applying a photosensitive resin to a substrate;

forming asperities which do not extend all the way through the resin in a first region of the photosensitive resin by using a first photomask and exposing at least part of the first region using said first photomask;

forming contact holes in a second region of the photosensitive resin using a second photomask different than the first photomask, and exposing at least part of the second region using said second photomask;

developing the exposed photosensitive resin;

heat treating the developed photosensitive resin;

forming a reflective electrode on the heat treated photosensitive resin over asperities so that said reflective electrode is in communication with at least one switching element through at least one of the contact holes; and

wherein exposure amounts using the first and second photomasks are the same.

19. (Amended) A method of manufacturing a liquid crystal display apparatus having, on one of a pair of substrates disposed so as to be opposed with a liquid crystal layer therebetween, a reflecting film for reflecting incident light from the other substrate, comprising:

applying a photosensitive resin on said one of the substrates;

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in order to form asperities in a first region of the applied photosensitive resin film which do not extend all the way through the photosensitive resin and to form a contact hole in a second region of the applied photosensitive resin film, exposing at least part of the first region with various integrals of exposure amounts using a first photomask so that the photosensitive resin in the first region is left in respective different film thicknesses, and exposing at least part of the second region with an integral of exposure amount different from those for the first region using a second photomask, wherein each of said first and second photomasks comprise both light transmitting portions for transmitting illuminance and light intercepting portions for blocking illuminance so that the asperities and contact hole are formed based upon arrangement of the light transmitting portions and light intercepting portions in the photomasks;

developing the exposed photosensitive resin;

heat-treating the developed photosensitive resin; and

forming a reflecting film on the heat-treated photosensitive resin so that the reflecting film is in electrical communication with a switching element through said contact hole.

Please add the following new claims:

22. (New) A method of making a reflective liquid crystal display, the method comprising:

applying a photosensitive resin to a substrate;
forming asperities which do not extend all the way through the resin in a first region of the photosensitive resin by using a first photomask and exposing at least part of the first region using said first photomask;
forming contact holes in a second region of the photosensitive resin using a second photomask different than the first photomask, and exposing at least part of the second region using said second photomask;
developing the exposed photosensitive resin;
heat treating the developed photosensitive resin;
forming a reflective electrode on the heat treated photosensitive resin over asperities so that said reflective electrode is in communication with at least one switching element through at least one of the contact holes; and
wherein each of said first and second photomasks comprise both light transmitting portions for transmitting illuminance and light intercepting portions for blocking illuminance so that the asperities and contact hole are formed based upon arrangement of the light transmitting portions and light intercepting portions in the photomasks.

23. (New) The method of claim 22, wherein uniform and low-illuminance exposure is performed so as to expose the photosensitive resin using the first photomask,